



PTO-1449 Equivalent

Second LIST OF PRIOR ART CITED BY APPLICANT
(Filed on January 20, 2004)

GK-OEH-171 / 500814.20073

Applicant(s): **Max Christian SCHUERMANN, et al.**Application No. **10/672,110**Group: **2878**Filed: **September 26, 2003**

Examiner:

U.S. PATENT DOCUMENTS

Exam. Init		Document Number	Date	Name	Class	Sub-Class	Filing Date Appropriate
	AA						
	AB						
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FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	CLASS	Sub-Class	Translation YES	Translation NO
	AL							
	AM							
	AN							
	AO							
	AP							

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

OG	AT	XP-001111378 / Research Disclosure, July 2001, 1146 (2 sided page) 447085 "Reflectometer for EUV lithography components"
OG	AU	Microelectronic Engineering 61-62 (2002) pages 145-155, "Characterization of optics and masks for the EUV lithography" Valérie Paret, et al.
OG	AV	11C-2-1, "Development of EUV reflectometer using a laser-plasma x-ray source Hiroyuki Kondo, et al. (1 page/34)
OG	AW	XP-0010183524 / Journal of x-ray Science and Technology 3, (1992) pages 283-299, "A Soft X-Ray/EUV Reflectometer Based in a Laser Produced Plasma Source, E. M. Gullikson, et al.
OG	AX	XP-000497187 / 8257b Journal of Vacuum Science & Technology B 12(1994) Nov/Dec, No. New York, NY, US, pages 3826-3832, "Multilayer facilities required for extreme-ultraviolet lithography, D.L. Windt, et al.
OG	AY	Nuclear Instruments and Methods in Physics Research A 359 (1995) pages 151-154, Synchrotron radiation soft X-ray reflectometer and its physics results, Cui Mingqi, et al.
OG	AZ	XP-000920796 / Applied Optics, March 1998, Vol. 37, No. 7, pages 1243-1248, "Laser-produced lithium plasma as a narrow-band extended ultraviolet radiation source for photoelectron spectroscopy", G. Schriever, et al.

Examiner:

Date:

06/07/05

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

LIST OF PRIOR ART CITED BY APPLICANT
(Filed on September 26, 2003)

Docket No. GK-OEH-171 / 500814.20073

Applicant(s): Max Christian SCHUERMAN, Thomas MISSALLA and Bernd SEHER

Application No. 10/672,110

Group:

Filed: concurrently herewith - September 26, 2003

Examiner:

U.S. PATENT DOCUMENTS

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	AA						
	AB						
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	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	CLASS	Sub-Class	Translation YES	NO
OG	AL	199 48 264	11/08/2001	Germany			Abstract only	
	AM							
	AN							
	AO							
	AP							
	AQ							
	AR							
	AS							

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	AV	
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	AX	
	AY	
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Examiner: <i>Oluf Baker</i>	Date: 06/07/05
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